

On-Chip Transient Detection Circuit for System-Level ESD Protection in CMOS ICs

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Abstract—A new on-chip transient detection circuit for system-level electrostatic discharge (ESD) protection is proposed in this paper. The circuit performance to detect different positive and negative fast electrical transients has been investigated by HSPICE simulator and verified in silicon chip. The experimental results in a 0.13- μm CMOS process have confirmed that the proposed on-chip transient detection circuit can detect fast electrical transients during system-level ESD zapping. The proposed transient detection circuit can be further cooperated with power-on reset circuit to improve the immunity of CMOS IC products against system-level ESD stress.

I. INTRODUCTION

System-level ESD issue is an increasingly significant reliability issue in CMOS IC products [1]. This tendency results from the strict requirements of reliability test standards, such as system-level ESD test for electromagnetic compatibility (EMC) regulation. In the system-level ESD test standard of IEC 61000-4-2 [2], the electrical/electronic product must sustain the ESD level of +8kV (+15kV) under contact-discharge (air-discharge) test mode to achieve the immunity requirement of “level 4.” Such high-energy ESD-induced noises often cause damage or malfunction of CMOS ICs inside the equipment under test (EUT). It has been reported [3] that some CMOS ICs are very susceptible to system-level ESD stress, even though they have passed the component-level ESD specifications such as human-body-model (HBM) of $\pm 2\text{kV}$, machine-model (MM) of $\pm 200\text{V}$, and charged-device-model (CDM) of $\pm 1\text{kV}$.

To meet the system-level ESD specifications, two useful methods have been reported and investigated [4]–[6]. One effective method is to add some discrete noise-decoupling components or board-level noise filters into the printed circuit board (PCB) to decouple, bypass, or absorb the electrical transient voltage (energy) under system-level ESD test [4]. The other method to improve the system-level ESD immunity of CMOS ICs is to regularly check the system abnormal conditions by using an external hardware timer, such as retriggerable monostable multivibrator [5]. However, the additional discrete noise-bypassing components increase the total cost of microelectronics system. Therefore, an on-chip solution integrated with the CMOS ICs, but without adding additional discrete noise-decoupling components on the PCB, is strongly requested by IC industry.

In this paper, an on-chip transient detection circuit is proposed to detect the fast electrical transient under the system-level ESD test. The circuit performance to detect different positive and negative fast electrical transients has been investigated by HSPICE and verified in silicon chip. The experimental results in a 0.13- μm CMOS process have

confirmed that the proposed on-chip transient detection circuit can successfully detect fast electrical transients during system-level ESD zapping.

II. SYSTEM-LEVEL ESD TEST

In the test standard of IEC 61000-4-2 [2], two test modes have been specified: air-discharge test mode and contact-discharge test mode. Fig. 1 shows the measurement setup of the system-level ESD test with indirect contact-discharge test mode, which consists of a wooden table on the grounded reference plane (GRP). In addition, an isolation plane is used to isolate the EUT from horizontal coupling plane (HCP). The HCP are connected to the GRP with two 470k Ω resistors in series.

With the measurement setup in Fig. 1, the robustness of CMOS ICs in the EUT against the system-level ESD stress can be determined. The transient responses on power lines of CMOS ICs can be further analyzed and recorded by the oscilloscope. Thus, the circuit performance of the proposed transient detection circuit can be evaluated through this measurement setup.

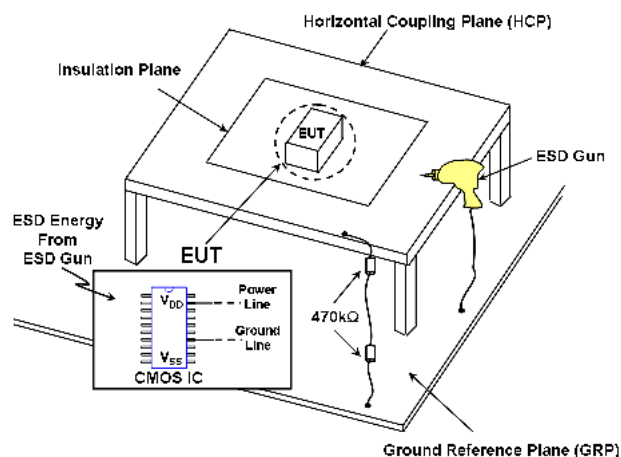


Fig. 1. Measurement setup for system-level ESD test with indirect contact-discharge test mode.

III. TRANSIENT DETECTION CIRCUIT

A. Circuit Structure

The proposed transient detection circuits realized with NMOS-reset and PMOS-reset functions are shown in Figs. 2(a) and 2(b), respectively. The detection circuits, composed of one latch and two coupling capacitances, are designed to memorize the occurrence of system-level ESD events and to sense the fast electrical transient on the power and ground

lines. The detection circuits shown in Figs. 2(a) and 2(b) are realized with 3.3V devices in a standard 0.13- μm CMOS process for 3.3-V circuit applications. The output signal of proposed on-chip transient detection circuit with NMOS-reset function is V_{OUT1} , and the output signal of proposed on-chip transient detection circuit with PMOS-reset function is V_{OUT2} .

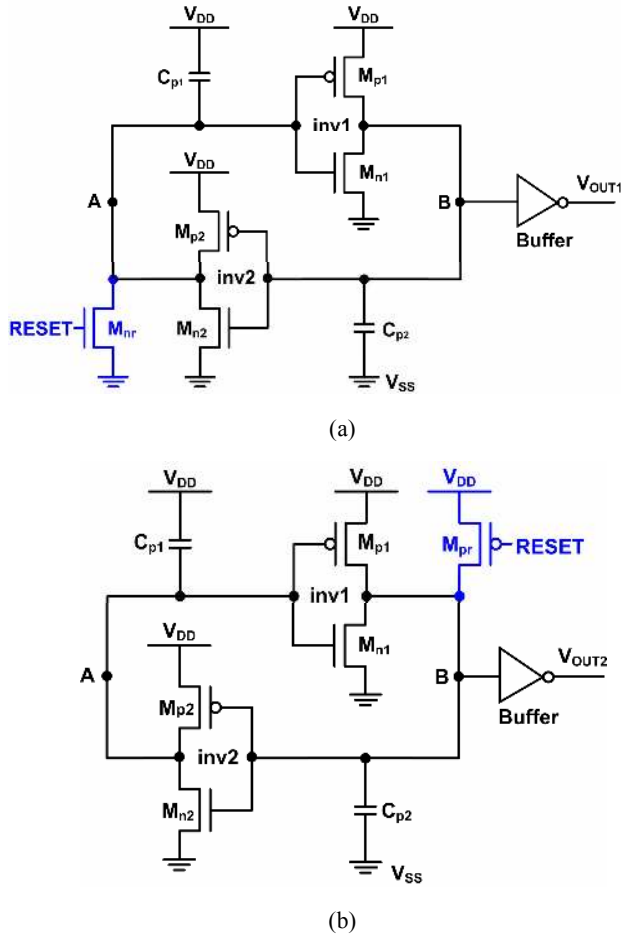


Fig. 2. The proposed on-chip transient detection circuits realized with (a) NMOS-reset, and (b) PMOS-reset, functions.

In order to increase the operation speed of detection circuit in Figs. 2(a) and 2(b) during fast electrical transient under the system-level ESD zapping, the device ratios (W/L) of latch should be adjusted. In order to pull down the voltage level of node B easily, the NMOS (M_{n1}) in the inverter1 (inv1) is designed with a larger W/L than that of PMOS (M_{p1}). On the contrary, to pull up the voltage level of node A easily, the PMOS (M_{p2}) in the inverter2 (inv2) is designed with a larger W/L ratio than that of NMOS (M_{n2}). In order to enhance the sensitivity of the detection circuit to electrical transient, two capacitances (C_{p1} and C_{p2}) are added between the node A (B) and V_{DD} (V_{SS}). The capacitance C_{p1} is placed between the V_{DD} and the input of inv1 in order to sense fast electrical transient on V_{DD} . The capacitance C_{p2} is placed between the V_{SS} and the input of inv2 in order to sense fast electrical transient on V_{SS} . The NMOS (M_{nr}) in Fig. 2(a) and the PMOS (M_{pr}) in Fig. 2(b) are used to provide the reset function in order to avoid the metastable operation of the latch circuit. With the reset signal of 3.3V (0V), the node A (B) of the

detection circuit shown in Figs. 2(a) (Fig. 2(b)) can be initially set up to 0V (3.3V). In normal condition, the output (V_{OUT1} and V_{OUT2}) of the proposed transient detection circuits will be kept at logic “0”. When a system-level ESD event occurs, the fast transient noises injecting to the power lines (V_{DD} , V_{SS}) will change the output state from logic “0” to become logic “1”. Therefore, the system-level ESD event can be detected by the proposed detection circuits.

The sensitivity of the proposed transient detection circuit can be further analyzed by adjusting the device ratios (W/L) in the latch or changing the value of coupling capacitances.

B. Simulation

A simulation tool (HSPICE) is used to investigate the on-chip detection circuit performance under the system-level ESD test. In this simulation tool, a specific time-dependent voltage source given by

$$V(t) = V_a \cdot \sin(2\pi f(t - t_d)) \cdot \exp(-(t - t_d)D_a) \quad (1)$$

is used to apply an underdamped sinusoidal voltage on the power lines of the proposed transient detection circuits. In the following HSPICE simulation, with the proper parameters such as the applied voltage amplitude V_a , damping factor D_a , damping frequency f , and time delay t_d , the intended underdamped sinusoidal voltage can be constructed.

On the printed circuit board layout, the routing traces may be different for power lines and ground lines. This can cause different coupling paths from ESD stress source to V_{DD} and V_{SS} pins of the chip, as shown in Fig. 3. The different coupling paths will result in different coupling delay between V_{DD} and V_{SS} waveforms. Thus, the proposed transient detection circuit should be evaluated in the conditions, where there is some coupling delay influence on $V_{\text{DD}}/V_{\text{SS}}$.

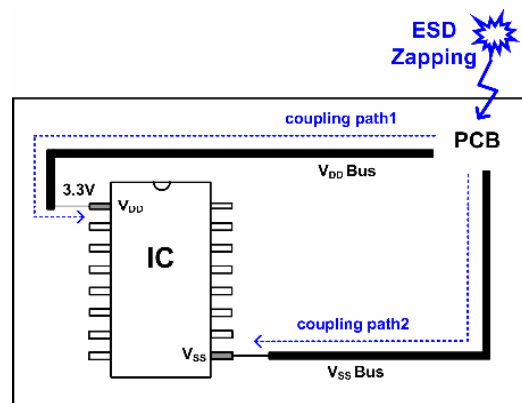


Fig. 3. Different coupling paths on printed circuit board from ESD stress source to V_{DD} and V_{SS} pins of ICs.

Under the condition of no coupling delay influence on $V_{\text{DD}}/V_{\text{SS}}$, the simulated V_{DD} , V_{SS} , V_{OUT1} , and V_{OUT2} waveforms of the proposed transient detection circuit with a positive-going underdamped sinusoidal voltage on both V_{DD} and V_{SS} are shown in Fig. 4. The positive-going underdamped sinusoidal voltage with V_a of +20V is used to simulate the positive ESD stress under the system-level ESD test. The V_{DD} voltage is initially kept at 3.3V with V_{SS} of 0V. Under ESD

stress, V_{DD}/V_{SS} begins to increase rapidly from 3.3V/0V. V_{OUT1} and V_{OUT2} are disturbed simultaneously during V_{DD}/V_{SS} disturbance. During this period, the transient detection circuit can detect the occurrence of disturbance on V_{DD}/V_{SS} . As a result, after V_{DD} finally returns to its normal voltage level of 3.3V, V_{OUT1} and V_{OUT2} will be changed from 0V to 3.3V.

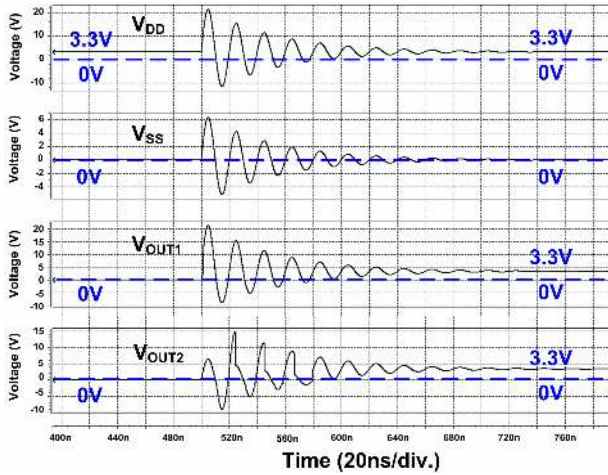


Fig. 4. Simulated V_{DD} , V_{SS} , V_{OUT1} , and V_{OUT2} waveforms of the proposed transient detection circuits with positive-going underdamped sinusoidal voltage on both V_{DD} and V_{SS} .

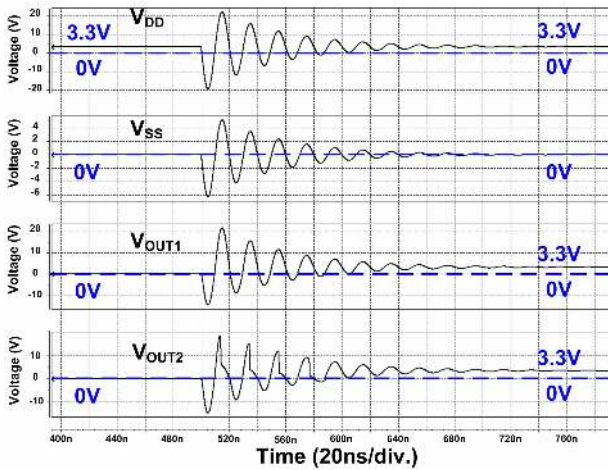


Fig. 5. Simulated V_{DD} , V_{SS} , V_{OUT1} , and V_{OUT2} waveforms of the proposed transient detection circuit with negative-going underdamped sinusoidal voltage on both V_{DD} and V_{SS} .

Under the condition of no coupling delay influence on V_{DD}/V_{SS} , the simulated V_{DD} , V_{SS} , V_{OUT1} , and V_{OUT2} waveforms of the proposed transient detection circuit with a negative-going underdamped sinusoidal voltage on both V_{DD} and V_{SS} are shown in Fig. 5. The negative-going underdamped sinusoidal voltage with V_a of -20V is used to simulate the negative ESD stress under the system-level ESD test. The V_{OUT1} and V_{OUT2} are influenced by the V_{DD}/V_{SS} disturbance through coupling paths. Finally, the outputs (V_{OUT1} and V_{OUT2}) of the transient detection circuits are changed from 0V to 3.3V.

The simulated V_{DD} , V_{SS} , V_{OUT1} , and V_{OUT2} waveforms of the proposed transient detection circuit with a coupling delay

of 8ns between V_{DD} and V_{SS} are shown in Fig. 6. During the period with fast transient stress, V_{OUT1} and V_{OUT2} are influenced by the V_{DD}/V_{SS} disturbance. Finally, V_{OUT1} and V_{OUT2} are pulled up to the voltage level of 3.3V. With a coupling delay between V_{DD} and V_{SS} , the proposed transient detection circuit can still memorize the occurrence of fast ESD transient stress.

From these simulations, the output states of detection circuits can be changed and kept at logic “1”, after the system-level ESD events. The sensitivity of the ESD detection circuits on the electrical transient stress can be analyzed by changing the coupling capacitances between the nodes A (B) and V_{DD} (V_{SS}) or by changing the device ratios (W/L) in the latch. The HSPICE simulation can be used to fine tune the device sizes in the proposed transient detection circuits to detect different transient levels.

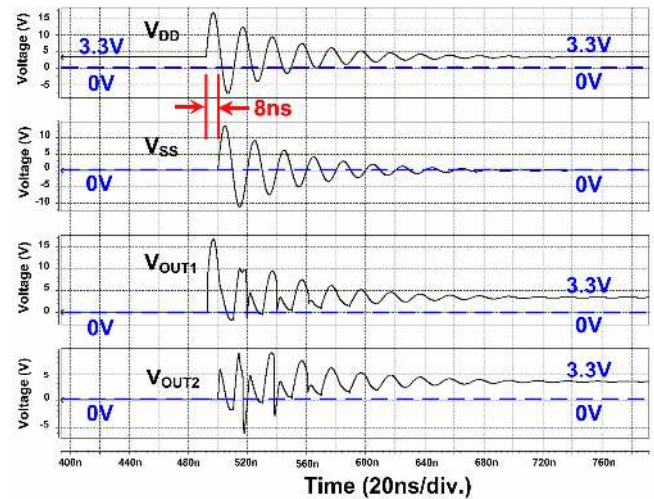


Fig. 6. Simulated V_{DD} , V_{SS} , V_{OUT1} , and V_{OUT2} waveforms of the proposed transient detection circuit with a coupling delay of 8ns between V_{DD} and V_{SS} .

IV. EXPERIMENTAL RESULTS

The proposed on-chip transient detection circuits have been fabricated in a 0.13- μm 1.2/3.3-V 1P8M CMOS process. The system-level ESD test with indirect contact-discharge test mode is used to experimentally verify the proposed transient detection circuit. With both positive and negative fast electrical transient, the measured V_{DD} transient response can be recorded by the oscilloscope. This can clearly indicate whether the detection circuit works correctly during the system-level test.

The measured V_{DD} and V_{SS} waveforms of the proposed transient detection circuit with ESD voltage of +500V zapping on the HCP under system-level ESD test are shown in Fig. 7. A coupling delay of ~5ns between V_{DD} and V_{SS} has been found in Fig. 7. This measured result is consistent with the design consideration shown in Fig. 3 and Fig. 6.

The measured V_{DD} , V_{OUT1} , and V_{OUT2} waveforms of the proposed transient detection circuit with ESD voltage of +1500V zapping on the HCP under system-level ESD test are shown in Fig. 8. V_{DD} begins to increase rapidly from the normal voltage (+3.3V). Meanwhile, V_{OUT1} and V_{OUT2} begin

to greatly increase with such high-energy ESD stress. During the period with disturbance on V_{DD} , V_{OUT1} and V_{OUT2} are disturbed simultaneously. Finally, the output voltage of the transient detection circuit is changed from 0V to 3.3V. As a result, the transient detection circuit can memorize the occurrence of the system-level ESD stress. The experimental results in Fig. 8 are consistent with the HSPICE simulation results in Fig. 4.

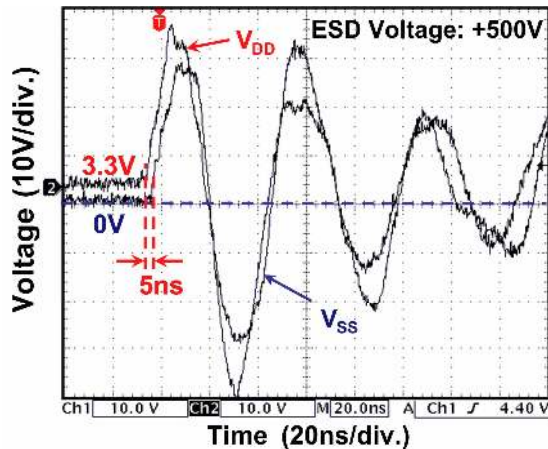


Fig. 7. Measured V_{DD} and V_{SS} transient responses with ESD voltage of +500V zapping on the HCP under system-level ESD test. There is a coupling delay of ~5ns between V_{DD} and V_{SS} waveforms in the initial period during the fast transient stress.

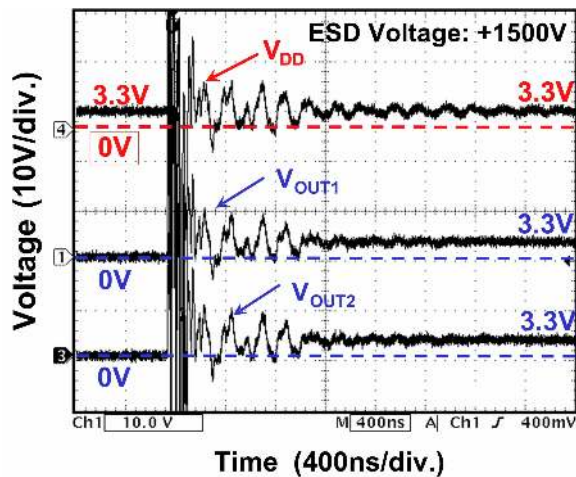


Fig. 8. Measured V_{DD} , V_{OUT1} , and V_{OUT2} transient responses with ESD voltage of +1500V zapping on the HCP under system-level ESD test.

The measured V_{DD} , V_{OUT1} , and V_{OUT2} transient waveforms of the proposed transient detection circuits with ESD voltage of -1500V zapping on the HCP under system-level ESD test are shown in Fig. 9. During V_{DD} disturbance, V_{OUT1} and V_{OUT2} are disturbed simultaneously. Obviously, V_{OUT1} and V_{OUT2} are finally pulled up to the 3.3V after the fast electrical noise.

The circuit performance of the transient detection circuit under the system-level ESD test has been proved by both the experimental results in silicon chip and the HSPICE simulation. From the experimental results, the proposed transient detection circuit can indeed memorize the occurrence of system-level ESD stress.

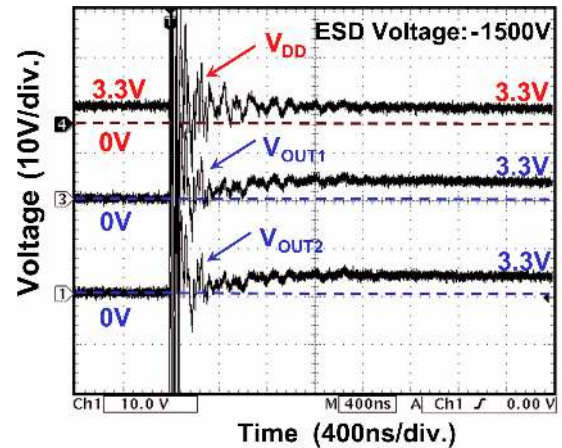


Fig. 9. Measured V_{DD} , V_{OUT1} , and V_{OUT2} transient responses with ESD voltage of -1500V zapping on the HCP under system-level ESD test.

V. CONCLUSION

A new transient detection circuit for system-level ESD protection has been implemented in a CMOS 0.13- μm process. By using one latch logic gate and two coupling capacitances, the on-chip transient detection circuit can be designed to detect the fast electrical transient during the system-level ESD zapping. The circuit performance under different positive and negative fast electrical transient has been also investigated by HSPICE. The experimental results in silicon chip have confirmed that the proposed on-chip transient detection circuit can detect fast electrical transients during system-level ESD zapping. The proposed transient detection circuit can be further combined with firmware design and power-on reset circuit to provide an effective solution to solve the system-level ESD issue in microelectronics system with CMOS ICs.

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